



<b>Session Title:</b>	<b>[TuA2] Challenges and Opportunities in CMP</b>
<b>Session Date:</b>	<b>November 12 (Tue.), 2024</b>
<b>Session Time:</b>	<b>14:55-16:35</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F, Paradise Hotel Busan)</b>
<b>Session Chair:</b>	<b>Prof. Keon-Soo Jang (Univ. of Suwon, Korea)</b>

[TuA2-1] [Invited]

14:55-15:25

**Planarization for Advanced Semiconductor Processing: Challenges and Opportunities**

Hyo-Chol Koo and Jiho Kang (SK hynix Inc., Korea)

[TuA2-2] [Invited]

15:25-15:55

**Eco-Innovations in Semiconductor Manufacturing: Sustainable CMP Approaches for the Next Generation**

Jihoon Seo (Clarkson Univ., USA)

[TuA2-3]

15:55-16:15

**Monitoring of Slurry Components and Concentrations for CMP Process via Raman Spectroscopy**

Eun Su Jung and Sung Gyu Pyo (Chung-Ang Univ., Korea)

[TuA2-4]

16:15-16:35

**Sulfate Radical Oxidation for Enhancing Polishing-Rate for WC-Film Chemical Mechanical Planarization**

Man-Hyup Han, Myung-Hoe Kim, Hyun-Sung Koh (Hanyang Univ., Korea), Jin-Hyung Park (ENF Tech. Inc., Korea), and Jae-Gun Park (Hanyang Univ., Korea)